

MONDAY 23rd January		
8:45-9:00	Welcome by Prof. Mato Knez	
Session I		
9:00-10:00	Plenary Session	Maarit Karppinen Department of Chemistry, Aalto University, Finland ALD/MLD of novel inorganic-organic hybrid materials and superlattices: from fundamentals to energy applications
10:00-10:30	Oral	Kevin Van de Kerckhove Department of Solid State Sciences, Ghent University, Belgium Molecular Layer Deposition for Applications in Lithium-ion Batteries
10:30-11:00	Oral	Kristian Blindheim Lausund Department of Chemistry University of Oslo, Norway Crystallization of hybrid films to form the metal-organic framework UiO-66
Coffee Break		
Session II		
11:30-12:15	Invited	Ola Nilsen Department of Chemistry, University of Oslo, Norway From ALD to MLD
12:15-12:45	Oral	Jenna Penttinen Department of Chemistry, Aalto-University, Finland Atomic/Molecular Layer Deposition of s-block Carboxylate
12:45-13:15	Oral	Rob Ameloot Center for Surface Chemistry and Catalysis, University of Leuven, Belgium Porous crystals from the vapor phase: chemical vapor deposition of metal-organic frameworks (MOF-CVD)
Lunch Break		
Session III		
14:30-15:15	Invited	TBC
15:15-15:45	Oral	Fieke van den Bruele Holst Centre/TNO, High Tech Campus Eindhoven, The Netherlands Challenges in scaling Molecular Layer Deposition processes
15:45-16:15	Oral	Mercedes Vila Juárez. Coating Technologies S.L.-CTECHnano. San Sebastian, Spain New Trends of Industrial Coatings: Atomic Layer Deposition
16:15-17:30	Expert Discussion	

TUESDAY 24th
January

Session VI		
9:15-10:00	Invited	Hayrensa Ablat Tyndall National Institute, University College Cork, Ireland Acrylate-based hybrid thin films grown by Molecular Layer Deposition
10:00-10:30	Oral	Laura Svärd VTT Technical Research Centre of Finland, Espoo, Finland Low-temperature Molecular Layer Deposition using monofunctional aromatic precursors and ozone-based ring opening reactions
10:30-11:00	Oral	Noureddine Adjeroud Luxembourg Institute of Science and Technology, Luxembourg Atomic Layer Deposition of Metalcone
Coffee Break		
Session V		
11:30-12:15	Invited	David Muñoz-Rojas Laboratoire des Matériaux et du Génie Physique (LMGP), Grenoble, France Atmospheric Pressure Spatial Atomic Layer Deposition (AP-SALD): open air deposition of functional thin films at high rates
12:15-12:45	Oral	Itxasne Azpitarte CIC Nanogune Consolider, San Sebastián, Spain Improving the thermal and mechanical properties of Kevlar through MPI
12:45-13:15	Oral	Weike Wang CIC Nanogune Consolider, San Sebastián, Spain Doping of Polyaniline by means of vapor phase infiltration
Lunch Break		
Session VI		
14:30-15:15	Invited	TBC
15:15-15:45	Oral	Leva Momtazi Department of Chemistry, University of Oslo, Norway Future use of ALD scaffolds for tissue engineering
15:45-16:15	Oral	Pirjo Heikkilä VTT Technical Research Centre of Finland Ltd. Finland Core-shell carbon-ceramic hybrid fibres by electrospinning and atomic layer deposition (ALD)
16:15-17:30	Labs Visit	

WEDNESDAY
25th January

IBERIAN ALD

Session VII

9:15-10:00	Invited	Lifeng Liu International Iberian Nanotechnology Laboratory (INL), Braga, Portugal Atomic layer deposition of molybdenum sulfide for use as an electrocatalyst in electrochemical and photoelectrochemical water splitting
10:00-10:30	Oral	Álvaro Blanco Instituto de Ciencia de Materiales de Madrid ICMM-CSIC, Madrid, Spain Fabrication of Photonic Structures with Atomic Layer Deposition
10:30-11:00	Oral	Mariona Coll Institut de Ciència de Materials de Barcelona, ICMA-B-CSIC, Barcelona, Spain Epitaxial complex oxide thin films by atomic layer deposition

Coffee Break

Session VIII

11:30-12:15	Invited	Rui F. Silva CICECO - Aveiro Institute of Materials, Department of Materials and Ceramic Engineering, Aveiro, Portugal Manganese oxide/carbon nanotubes heterostructures for electrochemical capacitors
12:15-12:45	Oral	Maria Carmen Morant-Miñana CEIT and Tecnun (University of Navarra), CIC nanoGUNE Consolider, San Sebastián, Spain Atomic Layer Deposition of AZO IDEs for monitoring stimuli-responsive ionogels
12:45-13:15	Oral	Fan Yang CIC Nanogune Consolider, San Sebastián, Spain ALD-infiltration/MLD fundamental study: Interaction of TMA with different functional groups (-OH, NH ₂ and NO ₂)

CLOSURE